L Number	Hits	Search Text	DB	Time stamp
-	22	(("20020042029") or ("6040965") or	USPAT;	2003/03/07 17:11
		("5932396") or ("6480355") or ("5747198")	US-PGPUB	
		or ("6289578") or ("5725997") or		
!		("6483664") or ("6501618") or ("6504678")		
		or ("20010010885") or ("20010019036") or		
: 		("20010027029") or ("6465149") or		
		("20010019465") or ("20010035355") or		
		("20010038517") or ("20010035343") or		
		("20020037476") or ("20020071211") or ("20030007295") or ("20020187430")).PN.		
	61373		USPAT;	2003/03/07 17:59
	01373	resistive) or magnetoresistive or	US-PGPUB;	2003,03,0, 1,103
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.		
_	2793		USPAT;	2003/03/07 18:00
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)		0000 (00 (00 10 00
-	2003	1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	USPAT;	2003/03/07 19:27
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))		
-	65	(((((magnetic adj head) or (magneto adj	USPAT;	2003/03/07 19:04
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))		

			T	
-	23		USPAT;	2003/03/07 19:03
İ		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
1		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
i		or (GMR same magneto\$15)).ti,ab.) and		
1		(resist or photoresist or photopolymer\$7		
:	i	or photoimag\$5)) and ((ash\$3 or (ash adj		
	İ	treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
ļ		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
1		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
1		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (((mill\$3 or ion		
		adj beam or FIB or RIE or ion adj etch\$3		
		or sputter\$3) or (lift adj off or liftoff		
1		or remov\$3 or etchback or etch\$3 adj		
1		back)) near5 (resist or photoresist or		
		imag\$3 or pattern\$3))) and ((heat\$3 or		
		bak\$3) with (resist or photoresist or	`	
1		imag\$3 or pattern\$3))		
-	.56		USPAT;	2003/03/07 19:02
		resistive) or magnetoresistive or	US-PGPUB;	
ļ	İ	magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
1		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
]		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
	1	littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (((mill\$3 or ion		
		adj beam or FIB or RIE or ion adj etch\$3		
	1	or sputter\$3) or (lift adj off or liftoff		
		or remov\$3 or etchback or etch\$3 adj	Ì	
		back)) near5 (resist or photoresist or		1
1	ł	imag\$3 or pattern\$3))	1	

- 33	((((((magnetic adj head) or (magneto adj	USPAT;	2003/03/08 15:24
- 33	l		2003/03/08 15:24
	resistive) or magnetoresistive or	US-PGPUB;	
	magnetophotoresistive or (magneto adj	EPO; JPO;	
	photoresistive) or (giant adj magneto\$15)	IBM_TDB	
	or (GMR same magneto\$15)).ti,ab.) and		•
	(resist or photoresist or photopolymer\$7		'
	or photoimag\$5)) and ((ash\$3 or (ash adj		-
	treat\$4) or etch\$3 or narrow\$3 or shrink\$3		1
	or shrunk\$3 or contract\$3 or small\$3 or		
	littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
	or trim\$4 or less\$5 or tight\$4) same		
	(resist or photoresist or imag\$3 or		
	pattern\$3))) and ((resist or photoresist		
	or imag\$3 or pattern\$3) same ((oxygen or		
	"O" or "O.sub.2") and (fluorine or		1
	fluoride or "F" or "F.sub.2" or ((nitrogen		
	or "N" or "N.sub.2") and (hydrogen or "H"		
	or "H.sub.2")))))) and (((mill\$3 or ion		
	adj beam or FIB or RIE or ion adj etch\$3		
	or sputter\$3) or (lift adj off or liftoff		
	or remov\$3 or etchback or etch\$3 adj		
	back)) near5 (resist or photoresist or		
	imag\$3 or pattern\$3))) not		
	<pre>((((((((magnetic adj head) or (magneto adj</pre>		
	resistive) or magnetoresistive or		
	magnetophotoresistive or (magneto adj		
	photoresistive) or (giant adj magneto\$15)		
	or (GMR same magneto\$15)).ti,ab.) and		
	(resist or photoresist or photopolymer\$7		
	or photoimag\$5)) and ((ash\$3 or (ash adj		
	treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
	or shrunk\$3 or contract\$3 or small\$3 or	, .	
	littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
	or trim\$4 or less\$5 or tight\$4) same		1
	(resist or photoresist or imag\$3 or		
	pattern\$3))) and ((resist or photoresist		
	or imag\$3 or pattern\$3) same ((oxygen or		
	"O" or "O.sub.2") and (fluorine or		
	fluoride or "F" or "F.sub.2" or ((nitrogen		
	or "N" or "N.sub.2") and (hydrogen or "H"		!
	or "H.sub.2")))))) and (((mill\$3 or ion		
	adj beam or FIB or RIE or ion adj etch\$3		
	or sputter\$3) or (lift adj off or liftoff		
	or remov\$3 or etchback or etch\$3 adj		
	back)) near5 (resist or photoresist or		
	imag\$3 or pattern\$3))) and ((heat\$3 or		
	bak\$3) with (resist or photoresist or		
	imag\$3 or pattern\$3)))		

- 9	(((((magnetic adj head) or (magneto adj	USPAT;	2003/03/07	19:05
1	resistive) or magnetoresistive or	US-PGPUB;		
1	magnetophotoresistive or (magneto adj	EPO; JPO;		
	photoresistive) or (giant adj magneto\$15)	IBM TDB		
1	or (GMR same magneto\$15)).ti,ab.) and	_		
1	(resist or photoresist or photopolymer\$7			
1	or photoimag\$5)) and ((ash\$3 or (ash adj			
1	treat\$4) or etch\$3 or narrow\$3 or shrink\$3			
1	or shrunk\$3 or contract\$3 or small\$3 or			
	littl\$3 or reduc\$3 or decreas\$3 or slim\$4			
1	or trim\$4 or less\$5 or tight\$4) same			
	(resist or photoresist or imag\$3 or			
	pattern\$3))) and ((resist or photoresist			
1	or imag\$3 or pattern\$3) same ((oxygen or			
	"O" or "O.sub.2") and (fluorine or			
1	fluoride or "F" or "F.sub.2" or ((nitrogen			
1	or "N" or "N.sub.2") and (hydrogen or "H"			
į	or "H.sub.2")))))) not (((((magnetic adj			
	head) or (magneto adj resistive) or			
	magnetoresistive or magnetophotoresistive			
ļ	or (magneto adj photoresistive) or (giant			
1	adj magneto\$15) or (GMR same			
ł	magneto\$15)).ti,ab.) and (resist or		1	
	photoresist or photopolymer\$7 or			
1	photoimag\$5)) and ((ash\$3 or (ash adj			
1	treat\$4) or etch\$3 or narrow\$3 or shrink\$3		Ī	
	or shrunk\$3 or contract\$3 or small\$3 or			
1	littl\$3 or reduc\$3 or decreas\$3 or slim\$4			
	or trim\$4 or less\$5 or tight\$4) same			
	(resist or photoresist or imag\$3 or			
	pattern\$3))) and ((resist or photoresist			
	or imag\$3 or pattern\$3) same ((oxygen or			
1	"O" or "O.sub.2") and (fluorine or			
	fluoride or "F" or "F.sub.2" or ((nitrogen			
	or "N" or "N.sub.2") and (hydrogen or "H"			
	or "H.sub.2")))))) and (((mill\$3 or ion			
	adj beam or FIB or RIE or ion adj etch\$3			
	or sputter\$3) or (lift adj off or liftoff			
	or remov\$3 or etchback or etch\$3 adj			
	back)) near5 (resist or photoresist or			
	imag\$3 or pattern\$3)))			

resismagne photo or (((resion resismagne) or photo or (resion resismagne) or (resismagne)	(magnetic adj head) or (magneto adj stive) or magnetoresistive or etophotoresistive or (magneto adj oresistive) or (giant adj magneto\$15) GMR same magneto\$15)).ti,ab.) and ist or photoresist or photopolymer\$7 notoimag\$5)) and ((ash\$3 or (ash adj c\$4) or etch\$3 or narrow\$3 or shrink\$3 or contract\$3 or small\$3 or l\$3 or reduc\$3 or decreas\$3 or slim\$4 or less\$5 or tight\$4) same ist or photoresist or imag\$3 or ern\$3)) not (((((magnetic adj head) magneto adj resistive) or etoresistive or magnetophotoresistive magneto adj photoresistive) or (giant magneto\$15) or (GMR same	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/10	15:26
magne photo treat or si litt: or treat or si litt: or treat or ir "O" of fluor or "I	eto\$15)).ti,ab.) and (resist or presist or photopolymer\$7 or pimag\$5)) and ((ash\$3 or (ash adj as\$4)) or etch\$3 or narrow\$3 or shrink\$3 or runk\$3 or contract\$3 or small\$3 or l\$3 or reduc\$3 or decreas\$3 or slim\$4 or less\$5 or tight\$4) same ast or photoresist or imag\$3 or ern\$3))) and ((resist or photoresist mag\$3 or pattern\$3) same ((oxygen or or "O.sub.2") and (fluorine or "O.sub.2") and (fluorine or "N.sub.2") and (hydrogen or "H.sub.2"))))) (magnetic adj head) or (magneto adj stive) or magnetoresistive or etophotoresistive or (magneto adj or esistive) or (giant adj magneto\$15) SMR same magneto\$15)).ti,ab.) and list or photoresist or photopolymer\$7 motoimag\$5)) and ((ash\$3 or (ash adj asynuk\$3 or etch\$3 or narrow\$3 or shrink\$3 arrunk\$3 or contract\$3 or small\$3 or	USPAT; US-PGPUB USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/08	
or sl litt. or t: (res: patte or ir	nrunk\$3 or contract\$3 or small\$3 or L\$3 or reduc\$3 or decreas\$3 or slim\$4 cim\$4 or less\$5 or tight\$4) same list or photoresist or imag\$3 or ern\$3))) and ((resist or photoresist mag\$3 or pattern\$3) same ((oxygen or			
fluor or "l or "l	ride or "F" or "F.sub.2" or ((nitrogen N" or "N.sub.2") and (hydrogen or "H" H.sub.2"))))))	IISPAT.	2003/03/08	15.24
- 2 ((((resistance) magne photo or (((resistance) or pl tread or sl litti or (resistance) resistance or (((resistance) resistance) resistance resistanc	(magnetic adj head) or (magneto adj stive) or magnetoresistive or etophotoresistive or (magneto adj oresistive) or (giant adj magneto\$15) GMR same magneto\$15)).ti,ab.) and list or photoresist or photopolymer\$7 notoimag\$5)) and ((ash\$3 or (ash adj c\$4) or etch\$3 or narrow\$3 or shrink\$3	US-PGPUB USPAT; US-PGPUB; EPO; JPO;		

-	0	(((((magnetic adj head) or (magneto adj	USPAT;	2003/03/08 18:00
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
ļ		or (GMR same magneto\$15)).ti,ab.) and	_	
i		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		1
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
	-	or trim\$4 or less\$5 or tight\$4) same		
	į	(resist or photoresist or imag\$3 or		
		pattern\$3))) not (((((magnetic adj head)		
		or (magneto adj resistive) or		
		magnetoresistive or magnetophotoresistive		1
		or (magneto adj photoresistive) or (giant		
1		adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or		
1		photoresist or photopolymer\$7 or		
		photoimag\$5)) and ((ash\$3 or (ash adj	1	
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		1
		or shrunk\$3 or contract\$3 or small\$3 or		1
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		1
		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) and ((resist or photoresist</pre>		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and		
		(napthoquinonediazide or		
		napthoquinonediazido)		
-	51	(resist or photoresist) and	USPAT;	2003/03/08 18:22
		(napthoquinonediazide or	US-PGPUB;	
		napthoquinonediazido)	EPO; JPO;	
			IBM_TDB	
-	3	((resist or photoresist) and	USPAT;	2003/03/08 18:24
		(napthoquinonediazide or	US-PGPUB;	
		napthoquinonediazido)) and (novolac or	EPO; JPO;	
		novolak) and dissolution near3 accelerat\$3	IBM TDB	
-	5	("4524121" "4745042" "5252831"	USPĀT	2003/03/10 09:27
		"5604073" "5800963").PN.		
-	4.5	(430/314,316,319-320,328-329).ccls. and	USPAT;	2003/03/10 15:51
		((oxygen or "O.sub.2") same ((nitrogen or	US-PGPUB;	
		"N.sub.2") and (hydrogen or "H.sub.2"))	EPO; JPO;	
1		same (ash\$3 or etch\$3))	IBM TDB	
_	25	((430/314,316,319-320,328-329).ccls. and	USPAT;	2003/03/10 17:36
		((oxygen or "O.sub.2") same ((nitrogen or	US-PGPUB;	
		"N.sub.2") and (hydrogen or "H.sub.2"))	EPO; JPO;	
		same (ash\$3 or etch\$3))) and (heat\$3 or	IBM TDB	
		bak\$3) same (resist or photoresist)		
1_	216	430/328.ccls. and (heat\$3 or bak\$3) same	USPAT;	2003/03/10 17:38
	210	(expos\$3) same (develop\$3)	US-PGPUB;	
		(CAPOSAS) Dame (GOVOTOPAS)	EPO; JPO;	
			IBM TDB	
	211	(430/328.ccls. and (heat\$3 or bak\$3) same	USPAT;	2003/03/10 17:39
-	211	(430/328.CCIS. and (nears of bakss) same (expos\$3) same (develop\$3)) not	US-PGPUB;	2003/03/10 17.39
		(((430/314,316,319-320,328-329).ccls. and	EPO; JPO;	
			IBM TDB	
		((oxygen or "O.sub.2") same ((nitrogen or	TDM-IDD	
		"N.sub.2") and (hydrogen or "H.sub.2"))		
		same (ash\$3 or etch\$3))) and (heat\$3 or		
1	1	bak\$3) same (resist or photoresist))	<u> </u>	1